| Ref # | Hits | Search Query | DBs | Default Operator | Plurals | Time Stamp |
|----------|------|--|---|---------------------|---------|------------------|
| L1 | 3237 | (356/399-401,614).CCLS. | US-PGPUB; USPAT; USOCR | OR | OFF | 2005/12/21 22:07 |
| L2 | 6977 | (430/5,22,30).CCLS. | US-PGPUB; USPAT; USOCR | Т; | | 2005/12/21 22:07 |
| L3 | 6238 | (355/53,55,77).CCLS. | US-PGPUB; USPAT; USOCR | OR | OFF | 2005/12/21 22:07 |
| L4 | 1196 | (250/548).CCLS. | US-PGPUB; USPAT; USOCR | OR | OFF | 2005/12/21 22:08 |
| L5 | 3144 | (438/5,7,14,16).CCLS. | US-PGPUB; USPAT; USOCR | OR | OFF | 2005/12/21 22:09 |
| L6 | 1984 | (1 2 3 4 5) and ((airtight\$4 air vacuum hermetic\$4 pressur\$4) same chamber\$4) | US-PGPUB; USPAT; USOCR | OR | OFF | 2005/12/21 22:09 |
| L7 | 1985 | (1 2 3 4 5) and ((airtight\$4 air vacuum hermetic\$4 pressur\$4) same chamber\$4) | US-PGPUB; USPAT; USOCR | OR | ON | 2005/12/21 22:12 |
| L8 | 617 | 7 and ((position\$3 edge contour) near (measur\$5 sens\$3 detect\$3)) | US-PGPUB; USPAT; USOCR | OR | ON | 2005/12/21 22:11 |
| L9 | 220 | 7 and (((position\$3 edge contour) near (measur\$5 sens\$3 detect\$3)) near (wafer semiconduct\$3 reticle mask photomask substrate)) | US-PGPUB; USPAT; USOCR | OR | ON | 2005/12/21 22:11 |
| L10 | 772 | ((airtight\$4 air vacuum hermetic\$4 pressur\$4) same chamber\$4) and (((position\$3 edge contour) near (measur\$5 sens\$3 detect\$3)) near (wafer semiconduct\$3 reticle mask photomask substrate)) | US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2005/12/21 22:12 |
| L11 | 582 | 10 and expos\$3 | US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2005/12/21 22:13 |
| L12 | 327 | 10 and (expos\$ near (device apparatus system)) | US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2005/12/21 22:14 |

| L13 | 154 | 12 not 9 | US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; | • | ON | 2005/12/21 22:14 |
|-----|-----|----------|--|---|----|------------------|
| | | | IBM_TDB | | | |